

# Texture in Electronic Applications

## Introduction and Overview

Mark Vaudin

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Registrants last week

13 Industry

13 National Labs

13 University

Administrative items

- Overview

- Materials: piezoelectrics, ferroelectrics, dielectrics, magnetics, metallization, etc
- Material forms: thin film (polycrystalline, epitaxial), bulk
- Producing/controlling texture: deposition methods and parameters; substrate effects; processing; seeding methods
- Measuring texture: techniques; accuracy; reciprocal space view
- Effects of texture: intrinsic; extrinsic; morphological
- Quote
  - “NIST is a user facility with which industry should become better acquainted.”

# Importance of texture

- Texture becomes important when materials properties are anisotropic (i.e. almost always!)
  - intrinsic (tensor) property, e.g. switching behavior in ferroelectrics.
  - extrinsic - typically linked with morphological texture or interface properties, e.g. grain boundary leakage current in dielectrics, fracture toughness
- In some cases the link between the texture of a material and its properties and application has been clearly demonstrated
- In others, texture has been observed (and may change during processing); however no link between texture and important properties has been demonstrated
  - is texture just “along for the ride”?
  - are we lacking the necessary insights to understand why it matters?

# Measurement Techniques

- X-ray diffraction
  - synchrotron, rotating anode, fixed tube
  - 4 circle goniometer, 2 circle (powder) diffractometer
  - conventional detectors, area detectors
  - Rietveld analysis of powder patterns
  - different correction methods for defocussing, absorption, etc
- Electron diffraction
  - EBSD: micro texture; grain size restrictions
  - TEM: highest resolution; specimen preparation !!!

## Measurement Techniques (cont)

- Neutron diffraction (posters)
  - very good for bulk but not thin films
- Other methods
  - stereology
    - morphological texture
    - relate to crystallographic texture
    - grain size restrictions
  - optical methods: birefringence, SHG, etc
    - Raman
    - AFM
  - any technique where response is function of orientation/texture

## Issues

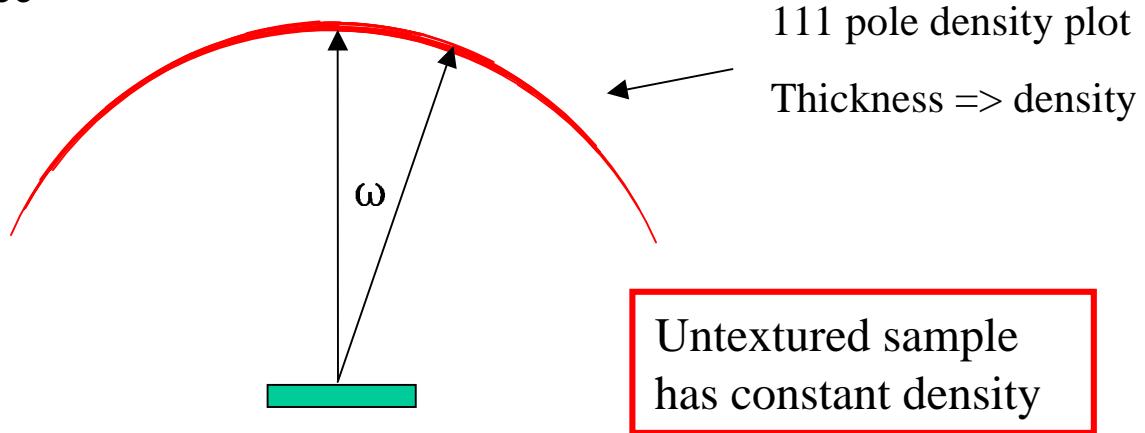
- new techniques
- effective use of existing methods
- need to understand techniques to understand results
- thin film standards
  - certified texture
  - certified thickness
  - need both

# Applications and challenges

- performance enhancement by texture optimization
- texture as a monitoring tool
- measurement of random volume fraction
- the best technique for the job
- check techniques against each other
- fibre texture measurements using powder diffractometer
  - accuracy of measurements
  - effects of slit sizes
- reciprocal space analysis

# Measurement of texture

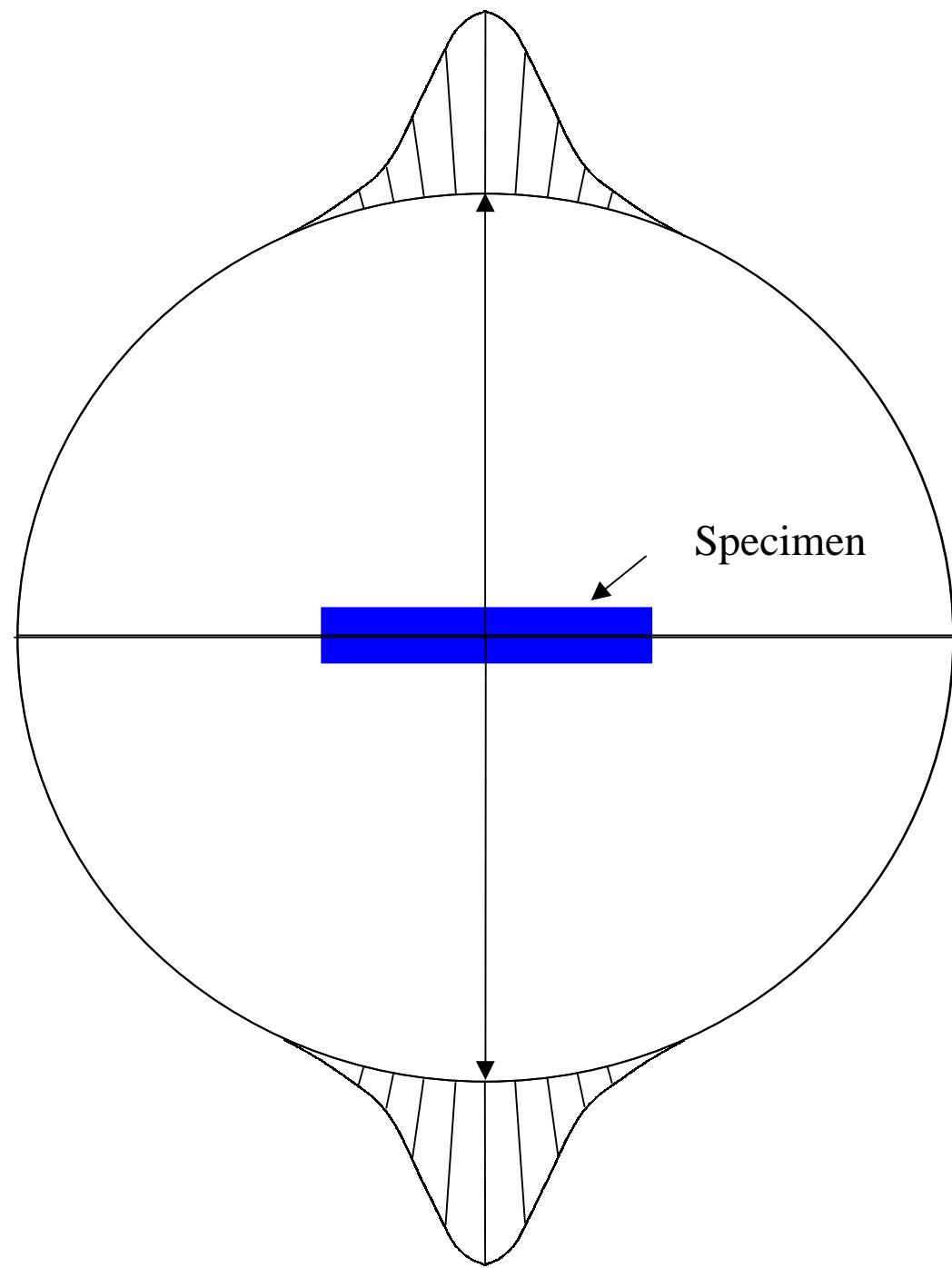
- Texture is function of relative orientation of crystal axes of grains in material with respect to specimen orientation
- Example: specimen with (111) preferred orientation normal to surface



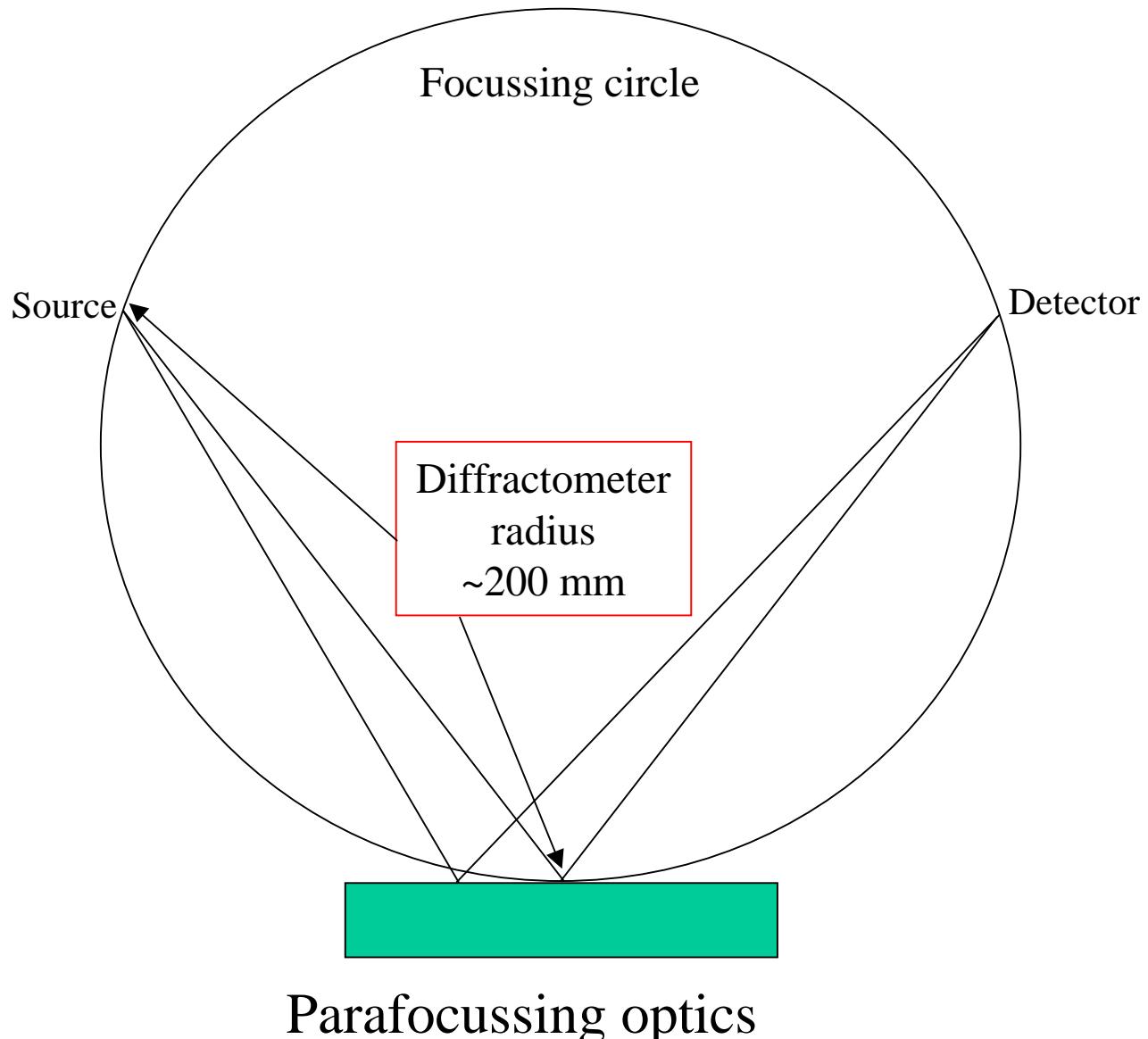
$$\text{Texture}(\omega) = \frac{\text{Volume fraction of sample at orientation } \omega}{\text{Volume fraction of untextured sample at } \omega}$$

- Diffracted x-ray intensity  $\propto$  diffracting volume
- Diffracted x-ray intensity( $\omega$ ) *could give* texture( $\omega$ )
- But there are problems:
  - defocussing
  - absorption
  - variation in irradiated area

## Schematic reciprocal space of textured specimen



# Defocussing



Scattering angle varies on flat specimen

Angle changes very small for 10 - 20 mm specimen

Tilt produces much larger angle changes

Measurement technique has been developed

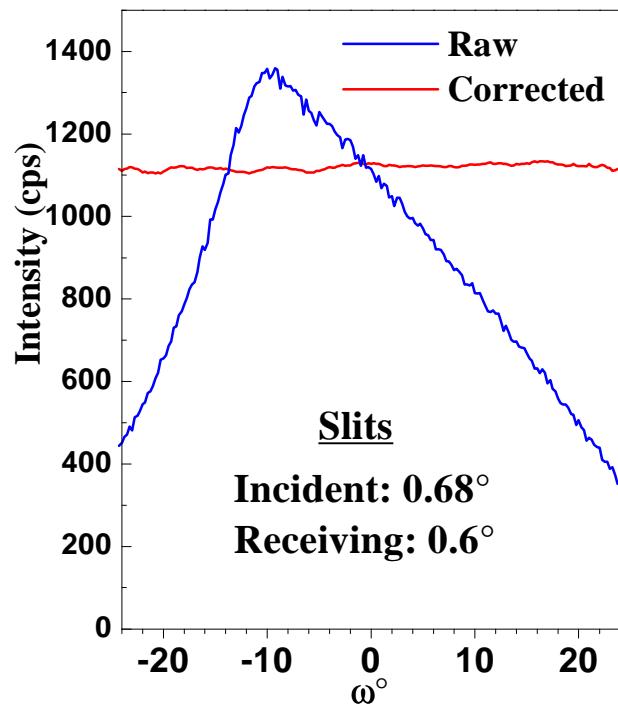
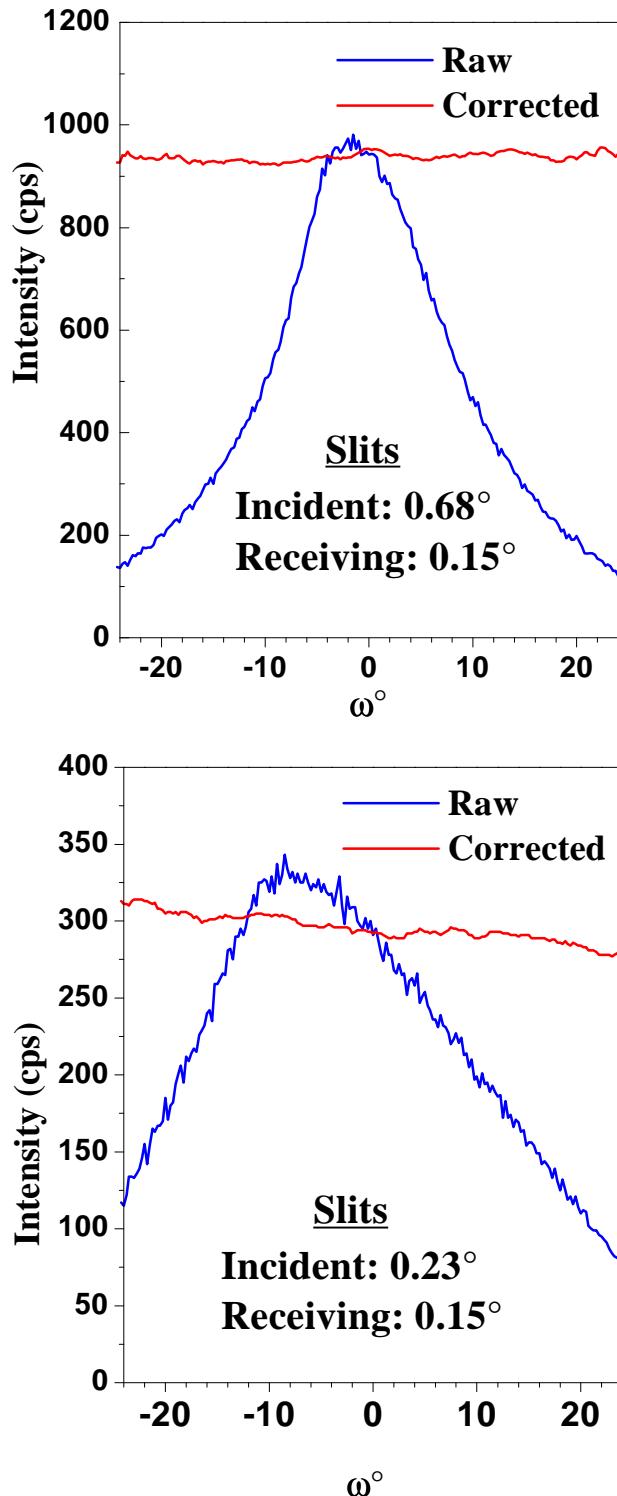
- **TexturePlus**

- software available:

<http://www.ceramics.nist.gov/webbook/TexturePlus/texture.htm>

- uses 2 circle diffractometer
- only rotates about one axis for each scan so best for fibre texture
- only can scan up to Bragg angle of peak so not good for weakly textured specimens
- as large an irradiated area as machine can do
- therefore high intensity
- good for thin films
- relatively fast

## Verification of correction factor using untextured alumina powder (SRM676)



**Peak:  $30\bar{3}0$**

**Data collected with different slit arrangements.**

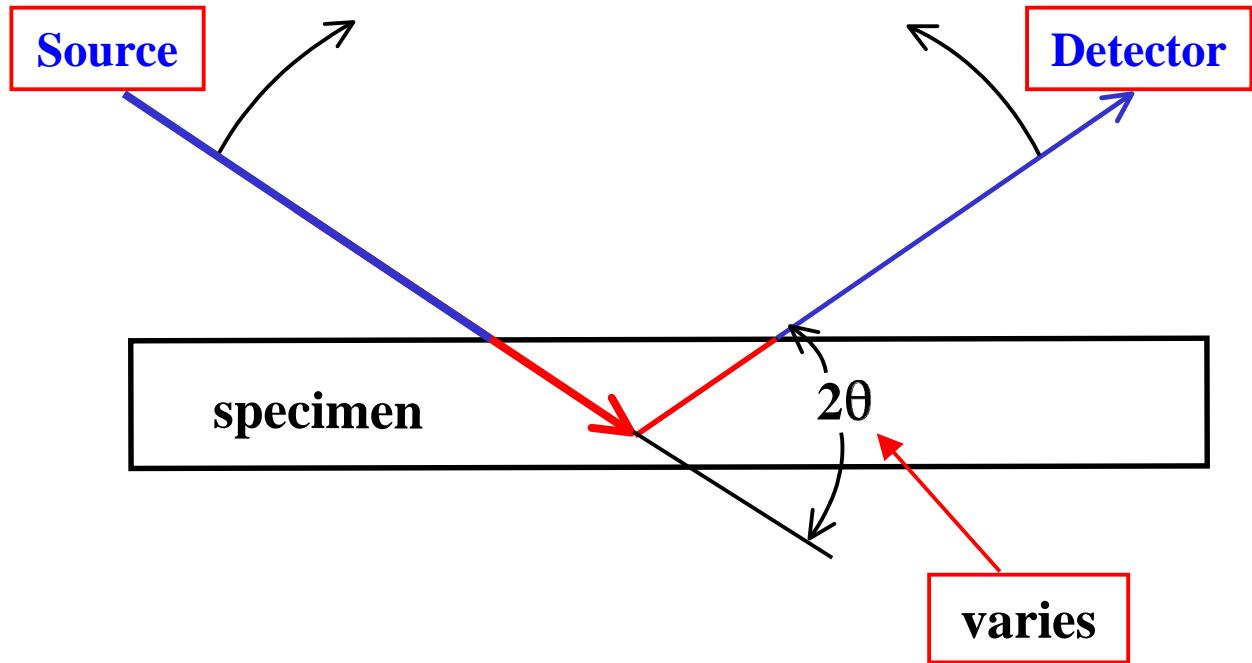
**Raw data: peaked**  
**Corrected curves: flat**  

- raw data can mislead
- corrections work

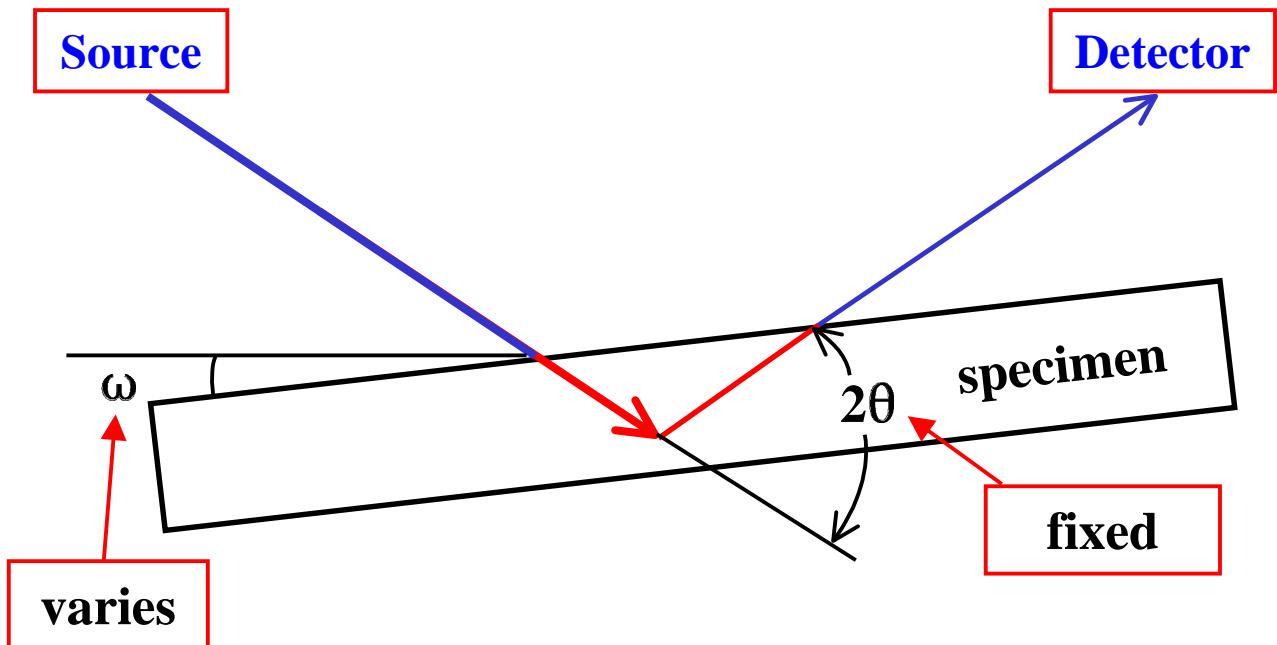
**Corrections large at high  $|\omega|$**   

- up to 5x

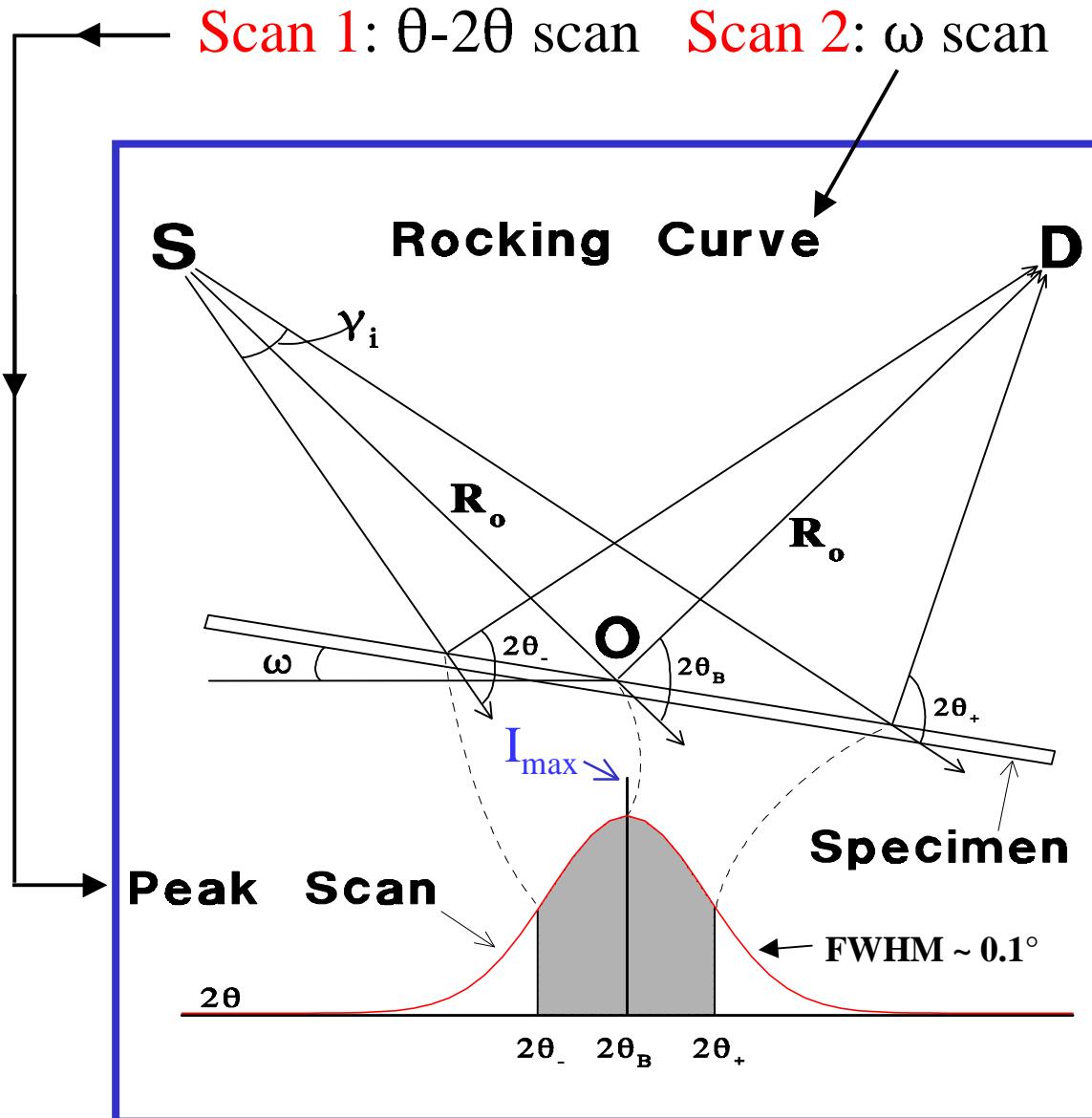
## $\theta$ - $2\theta$ scan



## $\omega$ scan



# Defocussing correction



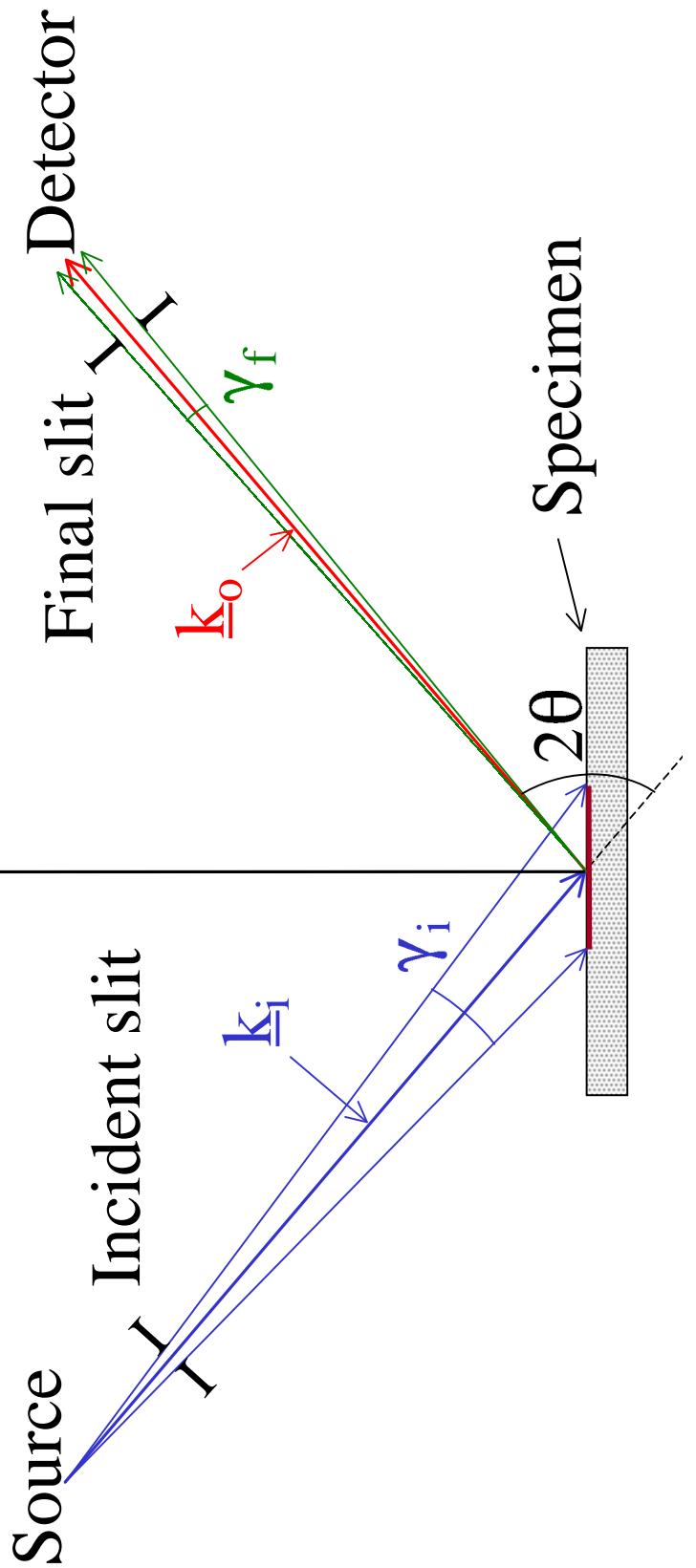
Calculate intensity from untextured specimen

$$I_{\text{rand}}(\omega) \propto \int_{-\gamma_i/2}^{\gamma_i/2} I_{\text{pk}}(2\theta(\omega, \gamma)) d\gamma$$

$|\underline{k}| = 1 / \lambda$

Divergent X-ray source geometry

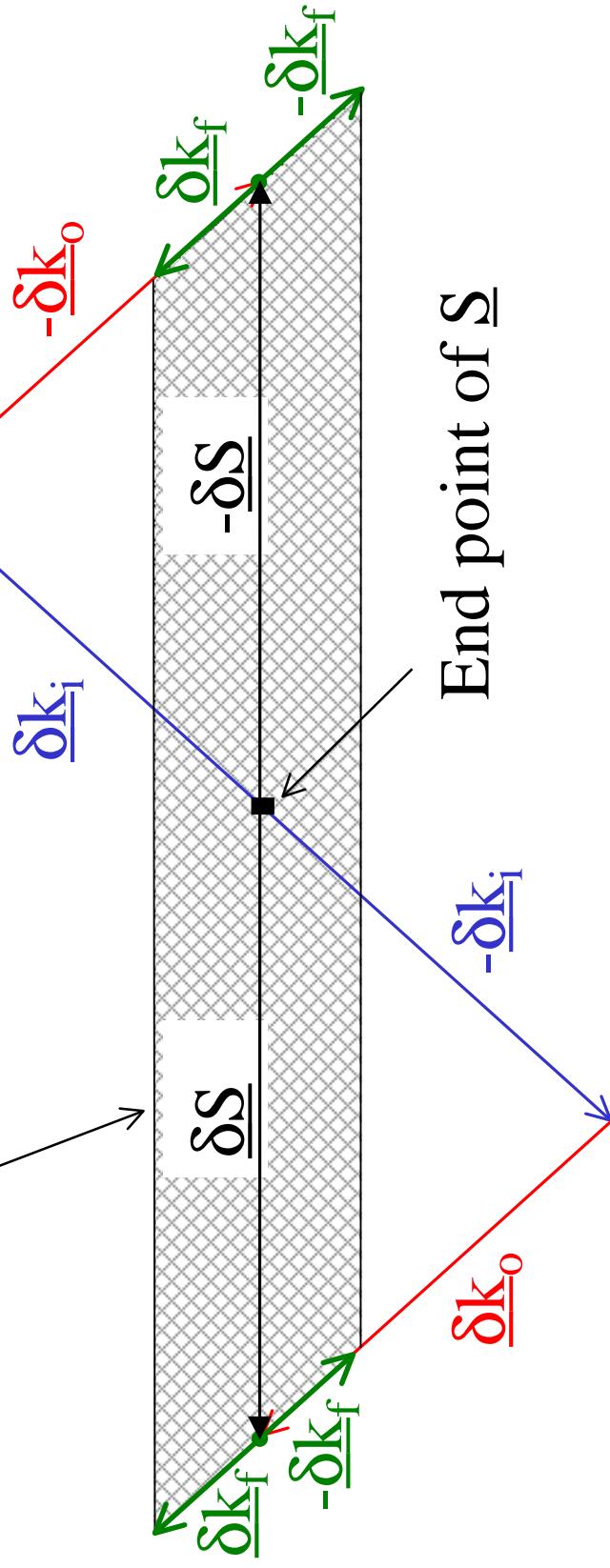
$$|\underline{S}| = \text{scattering vector} = \underline{k}_o - \underline{k}_i$$



# Reciprocal space schematic

Volume of reciprocal space integrated  
due to incident and final slits

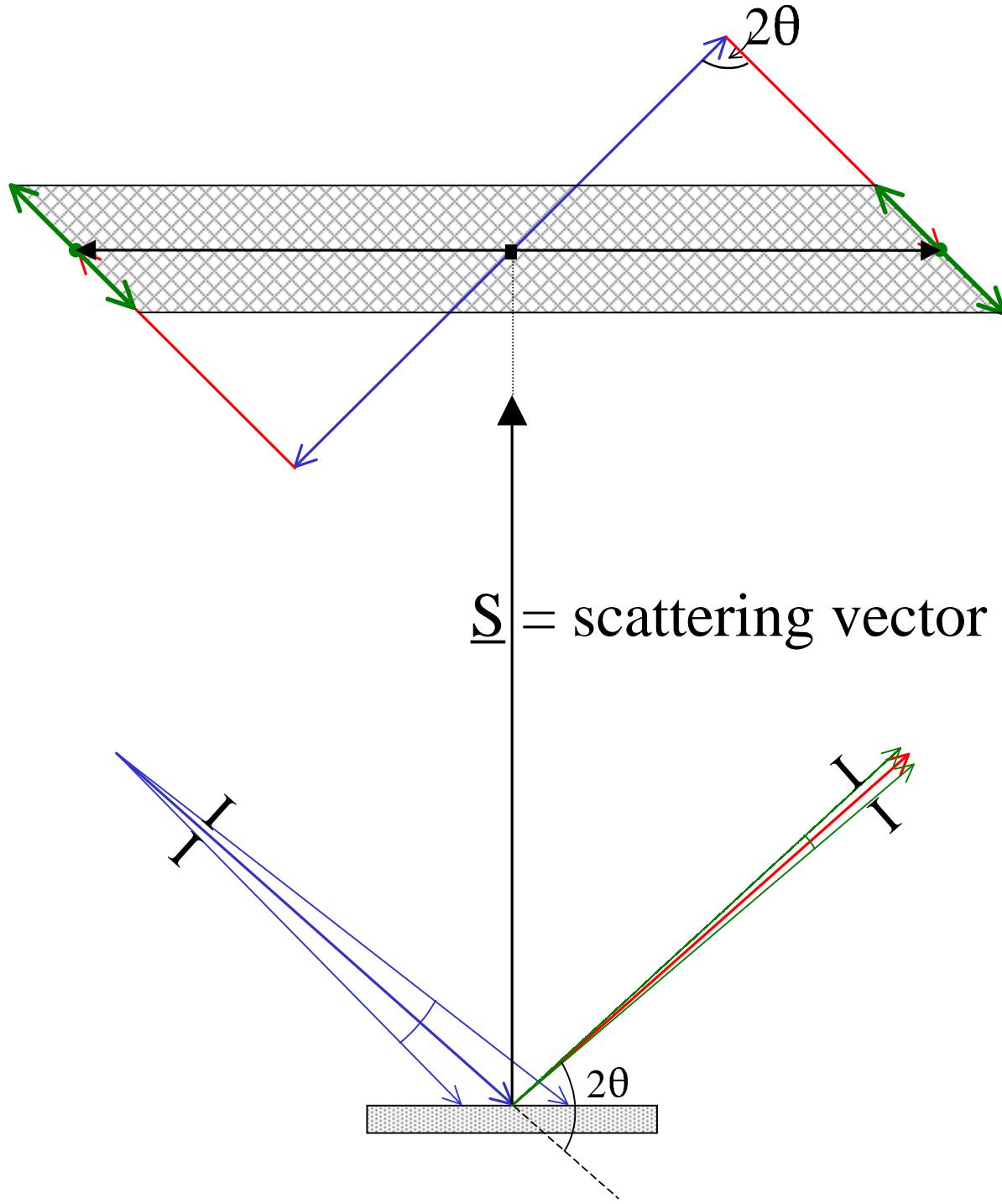
$2\theta$



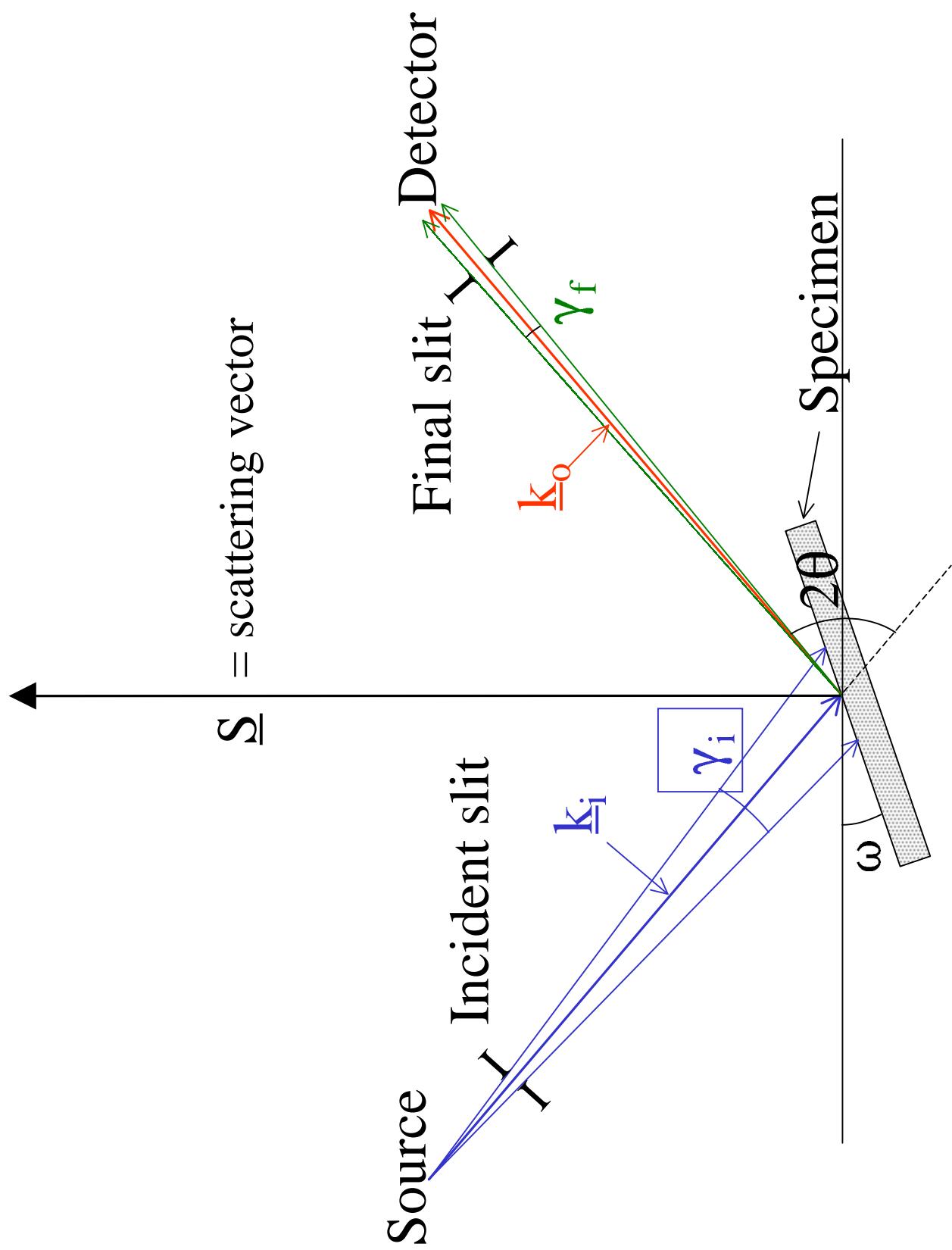
Width ( $2\delta S$ ):

- ~ texture measurement resolution
- determined mainly by  $\gamma$
- simple measurement with sapphire confirmed this

Top magnified  $\sim 100x$  relative to  $\underline{S}$

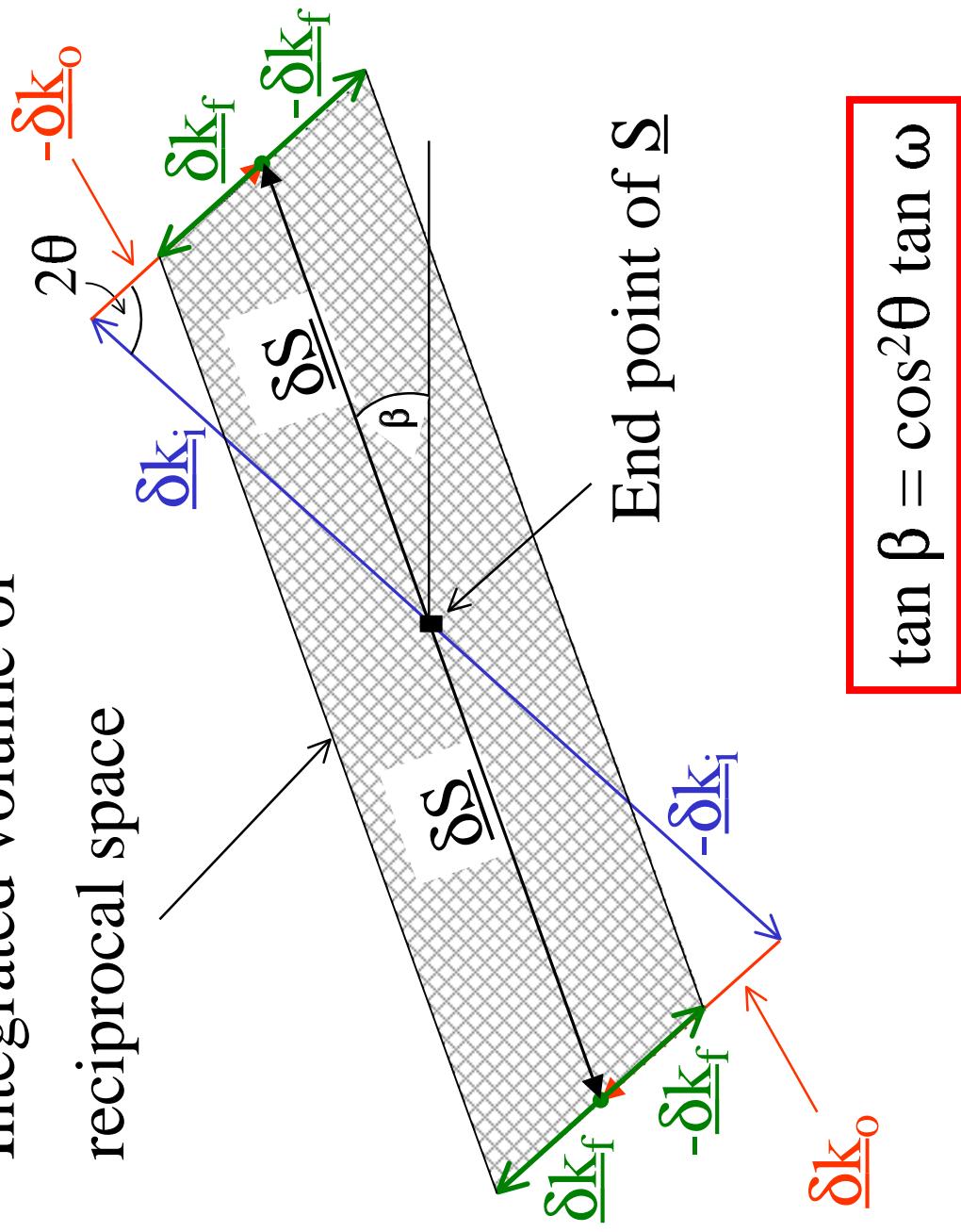


Tilted specimen



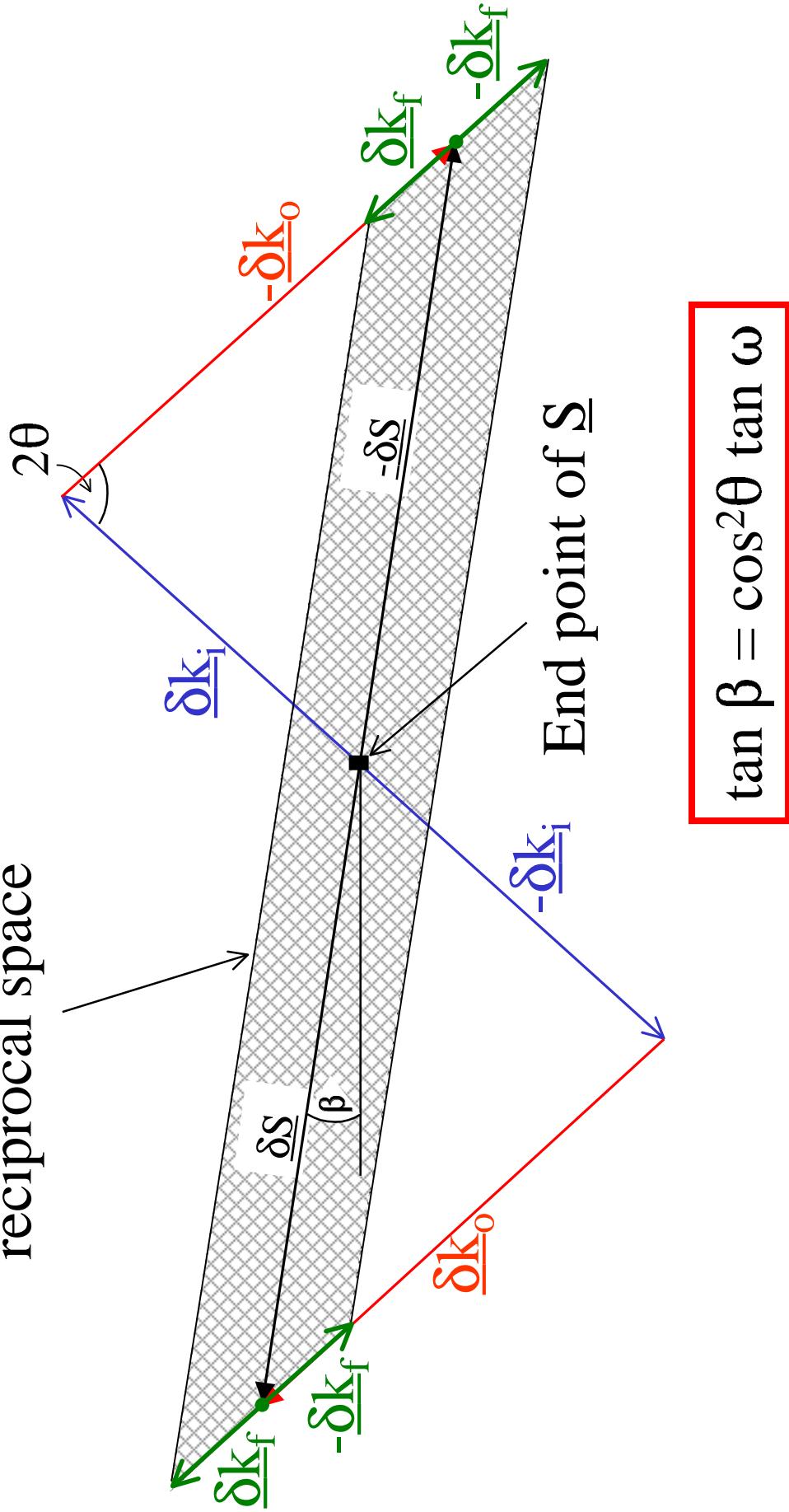
For  $\omega > 0$ :

Integrated volume of  
reciprocal space

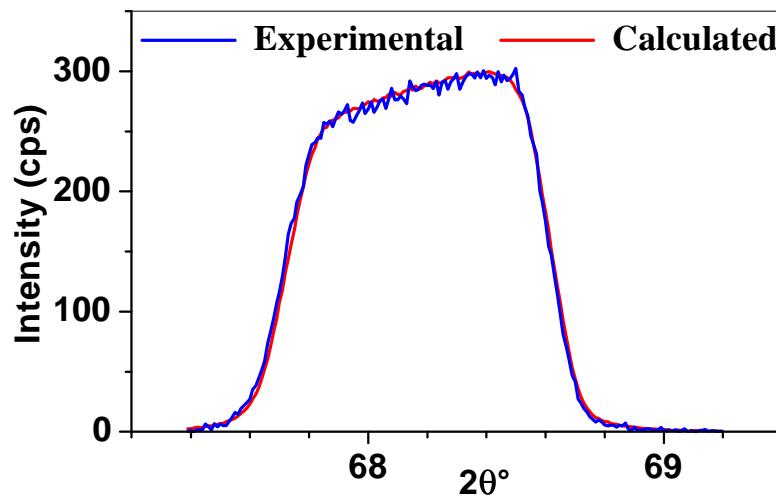
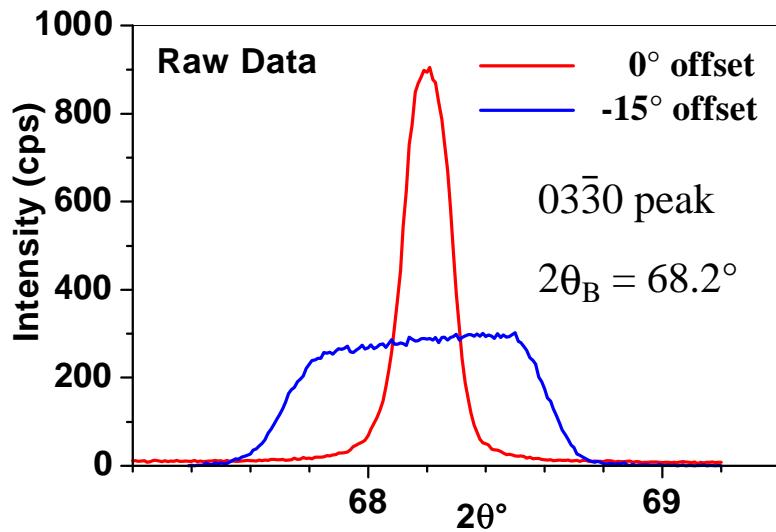
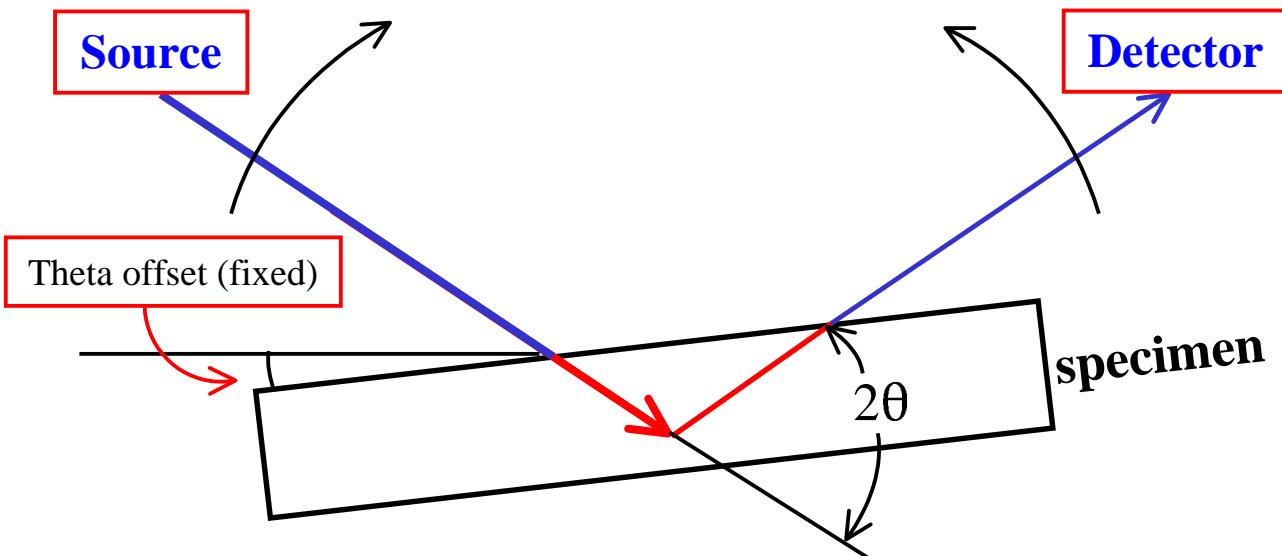


For  $\omega < 0$ :

Integrated volume of  
reciprocal space



# Theta-offset scans on SRM676 alumina powder



“Isometric form of SRM676 grains effectively eliminates preferred orientation effects”

# Powder pattern and rocking curve data for textured alumina

Specimen from Desi Kovar (University of Texas)

11 powder peak intensities divided by intensities from JCPDS 10-173

Note: analysis by Rietveld methods is more rigorous

Very approximate result: ~ 80% basal plane texture ~20% random

